TSMC-03-373

February 9, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
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Subject: Serial No. 10/719,722 11/21/03

Wen-Ting Chu et al.

A METHOD TO FORM FLASH MEMORY WITH VERY NARROW POLYSILICON SPACING

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on February 17 , 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date 2/17/04

U.S. Patent 6,342,451 to Ahn, "Method of Fabricating Floating Gates in Semiconductor Device," discloses methods to form a floating gate. Sidewall spacers are used to define a floating gate pattern.

U.S. Patent 6,514,868 to Hui et al., "Method of Creating a Smaller Contact Using Hard Mask," teaches a method to form a contact hole. A tapered hard mask is used to define a contact hole opening.

U.S. Patent 6,177,331 to Koga, "Method for Manufacturing Semiconductor Device," teaches an integrated circuit manufacturing method where a hard mask is tapered.

Sincerely,

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)	Application Number
TSMC-03-373	10/719,722
Applicant: Wen-Ting Chu et al.	
Filing Date: 11/21/03	Group Art Unit

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6,342,451	1/29/02	Ahn	438	706	4/24/00
	6,514,868	2/4/03	Hui et al.	438	713	3/26/01
	6,177,331	1/23/01	Koga	438	424	6/3/98

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES	Translation NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.